

Supplies Provided by NUFAB

Gowning

All required gowning supplies

Personal Protective Equipment (PPE)

All required PPE

Chemicals

Photoresists: SPR220.7, SU8-2050, SU8 25, SU8 3025, SU8 2, SU8-2010, S1813, S1805, LOR 1A, LOR 5A, AZ 5214E-IR, AZ P4620, 495 PMMA A8, Polyimide PI2545, AZ nLOF2035
Developers: MF319, AZ 400K (1:4 and concentrated), SU8 Developer, AZ 917MIF, AZ 300MIF

Resist Removers: Remover 1165, Nanostrip

Adhesion Promoter: HMDS, MCC Primer 80/20 (20% HMDS and 80% PM Acetate)

Solvents: Acetone, 2-Propanol

Etchants: Chrome Etchant, Buffered Oxide Etch 6:1 and 10:1, Aluminum Etchant, Nanostrip, HF, Fe₂O₃ Etchant, Copper Etchant, Gold Etchant TFA, KOH, TMAH 25%, HBr, HCl, Citric acid, H₂SO₄, HNO₃, H₃PO₄,

General Cleanroom Supplies

Silicon Wafers (various sizes)

Wafer and Mask Holders (various sizes)

Cleanroom Notebooks

Cleanroom Paper

Cleanroom Wipes (two types)

Storage Boxes

Petri Dishes

Aluminum Foil

Equipment Specific Supplies

AJA Sputter Targets: Cu, Al, Cr, Ti, Ni, W, Si, SiO₂, Si₃N₄, ZnO, ITO, PZT, Ag

AJA E-beam Evaporator: Crucibles for all materials

Denton Thermal Evaporator: Boats for all materials, chrome-coated tungsten rods

Evaporation Materials: Mo, W, Ag, Al, Cu, Ni, Ti, Cr, Au

Mask and Maskless Aligners: Blank Photomasks (for mask making) 4"x4" (Cr), 5"x5" (Cr), 3"x3" (Fe₂O₃), 4"x4" (Fe₂O₃), 5"x5" (Fe₂O₃)

Gases

Silane, Ammonia, Hydrogen, Dichlorosilane, Forming Gas (4%H₂, Balance N₂), UHP nitrogen, Oxygen, N₂O, CF₄, C₄F₈, CHF₃, Helium, SF₆, Argon, Liquid CO₂